Advanced Optical Metrology Solutions to Enable APC for CMP

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Nova IM portfolio for OCD

Process Control Trend

APC enabling OCD applications using NOVA
- FEOL : POST CMP correction
- RMG : W2W improvement with FB control
- BEOL : FF and FB process control

Summary
Nova IM Portfolio

Nova has 100% market share in pure play Foundries
Summary

- Reviewed CMP applications use process control with OCD on integrated metrology system

- Proved gate uniformity improvement with post CMP correction - L2L variation, WiW variation

- Gate Height variation in device structure improved at RMG using integrated metrology system

- Electrical resistance variability improved by using APC control of polish time using feed forward feed-back APC architecture
Contact Information

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THANK YOU

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